





BioSure Ozone CIS Clean Ice System

BioSure Clean Ice System (CIS) is the simplest and easiest solution to reduce bacteria and prevent biofilm growth in the water circulation system of ice machines. It can maintain the hygiene level of the ice machines at all times that has been tested by independent 3rd party laboratories.

This compact device is designed to be easily integrated with ice machines. It applied a revolutionary electrolytic active oxygen technology to generate ozone from water and dissolve into water, not only protecting the water pipeline against biofilm growth and pathogens in water, but also making the cleanest and safest ice for consumption. By using BioSure CIS, the cost of chemical for cleaning ice machine can be reduced.



Ozone water is the most natural disinfectant that can prevent the growth of biofilm. Compare with UV-C, ozone water is the best and all-around solution for clean ice.



99.99%1

Eliminates bacteria & viruses

Ozone oxidizes the cell body of bacteria and viruses, destroying their RNA directly. The sanitation speed is 3,000 times faster than chlorine.



Save 66%

Cost of chamical disinfactan

Reduce the expensive cost of chemical disinfectant, troublesome hand-cleaning process, and the damage risk of internal parts and components by strong chemical.

SPECIFICATIONS	
Model	CIS EOS7210-I
Control	Flow switch
Output ozone concentration	0.05 ppm
Water pipe connection	1/2"
Water quality	Filtered water
Ice machine capacity	Up to 1,800 lbs
Electric power	240V / 50Hz / 1ph, 15W
Consumable parts and lifespan ²	Ozone generator: 1 pc; approx. 1,000 hrs
Dimensions	73W x 118D x 131H mm
Net weight	0.395 kg

- 1. For details, please refer to Guangdong Detection Center of Microbiology test report on testing the reduction of bacteria using ozonated gas generated by Biolux SSS.
- 2. It is recommended to replace the consumable parts according to its lifespan listed in order to maintain the performance of the product. However, the actual replacement time should be accorded to actual usage.

^{*}Technologies applied are protected by one or more of these patents: US 8,308,9104 B2 / US 9,575,697 B2 / US 9,248,208 B2